

Notice of References Cited

Application/Control No.

09/096,858

Applicant(s)/Patent Under

Reexamination

NARWANKAR ET AL.

Examiner

Anh D. Mai

Art Unit

2814

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U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5910218	06-1999	Park et al.	118/719
	B	US-Pub-2001/0011740	08-2001	DeBoer et al.	257/306
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	S.C. Sun et al., A Novel Approach for Leakage Current Reduction of LPCVD Ta ₂ O ₅ and TiO ₂ Films by Rapid Thermal N ₂ O Annealing. IEDM 1994, pp. 333-336.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

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